



# WORKSHOP

## Maskless Direct Writing and 3D Lithography: Capabilities and Applications

● 5th April 2022 ●

### Location

"Salón de Actos"  
Universidad Politécnica de Madrid  
ETSI Telecomunicación  
Edificio C  
Avenida Complutense nº 30, "Ciudad Universitaria"  
28040 - Madrid (España)  
<https://goo.gl/maps/mWB2dKQeonqVQTCN9>

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### Participants



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# PROGRAM

## Maskless Direct Writing and 3D Lithography: Capabilities and Applications

### 10:00 Welcome Reception

Coffee & snacks

### 10:30 Introduction

Javier Martinez Rodrigo (Polytechnic University of Madrid, ISOM)

Nikos Ekizoglou (Irida Iberica)

### 11:00 Pushing the limits of direct write laser lithography

Daniel Braun/Wolfgang Meixner (Heidelberg Instruments)

### 11:30 Photolithography with Heidelberg uMLA: Main applications and challenges at MNFab-UMinho Laboratory

Manuel Silva & Rui Freitas (University of Minho).

### 12:00 Direct laser writing: industrial application experience

Rafael Vicent (Kerajet)

### 12:30 NanoFrazor lithography for advanced 2D and 3D nano-devices

Nils Goedecke (Heidelberg Instruments)

### 13:00 Direct laser writing as a core facility service

Pedro Barquinha (NOVA School of Science and Technology, FCT-NOVA)

### 13:30 Lunch

Food & drinks provided

### 14:30 MPO 100 – The new multi-user tool for 3D laser lithography and 3D microprinting with 2-photon polymerization (TPP)

Svenja Kohlhaas, (Multiphoton Optics GmbH)

### 15:00 Tabletop maskless writing; high speed and high performance in small footprint

Jorge Teniente, online (Public University of Navarra)

### 15:30 An Introduction to GenISys and GenISys Software Packages for lithography optimization

Mike Butler/Aditya Reddy, online (Genisys)

### 16:00 Closing

Stay for further discussions with coffee & snacks

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